Application of Data Matrix Verification Standards

Overview of Data Matrix Quality Standards and Measured Parameters
Application of Data Matrix Verification Standards

Data Matrix symbol verification at its most basic level eliminates the subjective quality determination that causes discord between marking and reading suppliers, and replaces those subjective opinions with objective measurements regarding the quality of the mark. Standards for verification take this process further to allow an even field of play for all measurement systems, such that cross-company and cross-industry applications may use an adopted standard to ensure the readability of symbols through their processes by setting limits based upon agreed standards. Topics of this white paper include:

- An introduction of the following standards:
  ISO/IEC 16022
  SAE AS9132
  ISO/IEC 15415
  AIM DPM-1-2006
  ISO/IEC 15434 and ISO/IEC 15418
- Parameters measured by each standard
- Examples of standard application, especially regarding the United States Department of Defense Item Unique Identification initiative MIL-STD-130.

Steve Twaddle, Microscan Systems, Inc.

ISO/IEC 16022

The Data Matrix symbology was invented by International Data Matrix, Inc. The Association for Automatic Identification and Mobility (AIM) promulgated the Data Matrix as a public standard in 1996 as "International Symbology Specification – Data Matrix." This standard was then adopted by ISO as standard ISO/IEC 16022 in May of 2000. The second revision of ISO/IEC 16022 was released in September of 2006. ISO/IEC 16022 Appendix N contains the first public standard for measurement of Data Matrix symbols. This standard includes measurement of the following parameters:

- Reference Decode
- Symbol Contrast
- Print Growth
- Axial Non-Uniformity
- Unused Error Correction

The lowest of the grades for the above parameters becomes the overall grade for the Data Matrix, and then the parameters are combined. The limitations of this standard are its over-reliance on contrast with regard to the overall quality of a symbol. This is because the standard is modeled after a guideline for linear (1D) symbols.

This standard has some application for symbols produced using black ink on white paper. However, very few marks of this type are used in the MIL-STD-130 application. The first version of MIL-STD-130 to include verification was MIL-STD-130L (October 10, 2003) which stated that marks must be graded as no less than "B" when generated and no less than "C" through the life of the mark, by the standards of ISO/IEC 16022.

Lighting requirements for ISO/IEC 16022 verification are not specified aside from the need for uniformity across the field of view. However, the standard recommends lighting from two or more sides at a 45° angle of incidence.

SAE AS9132

The Society of Automotive Engineers (SAE) first published Aerospace Standard (AS)9132 in 2002. This standard differs from other standards in two significant respects. AS9132 covers three specific marking methods: dot peen, laser etch, and electro-chemical etch. Also, AS9132 is a pass or fail standard that does not lend itself to process control, as there are no intermediate steps between success and failure. The parameters measured by AS9132 are:

**Dot Peening**
- Cell Fill
- Cell Size
- Dot Size Offset
- Dot Center Offset
- Angle of Distortion
- Dot Ovality
- Matrix Size

**Laser and Electro-Chemical Etching**
- Cell Fill
- Contrast
- Angle of Distortion
- Matrix Size
- Cell Size

If any one of the measured parameters for a mark fail then the overall grade for that mark is a failure. There are no lighting or imaging requirements stated in the AS9132 standard.

ISO/IEC 15415

The first ISO/IEC standard designed to address Data Matrix verification was ISO/IEC 15415 (June, 2004). This standard attempted to correct the insufficiencies of the previous stan-
Technology White Paper

dards by addressing the components of direct part marking. The parameters measured by ISO/IEC 15415 are:

• Symbol Contrast
• Axial Non-Uniformity
• Grid Non-Uniformity
• Unused Error Correction
• Fixed Pattern Damage
• Modulation
• Reference Decode
• Print Growth (may be reported but is not included as a grade component)

ISO/IEC 15415 specifies that the verification report must include the following information, with each element separated by a forward-slash character:

• Grade (Arithmetic mean to one decimal place of the grades measured from all images)
• Aperture (Diameter of the artificial aperture to the nearest thousandth of an inch)
• Light (Wavelength in nanometers)
• Angle (Assumed to be 45° and only reported if different than 45°)

One of the requirements of ISO/IEC 15415 is capturing five images each taken at 72° (± 5°) from each other, such that the symbol is measured at five orientations through one complete rotation. Another limitation of ISO/IEC 15415 is its over-sensitivity to minute changes in grayscale across the symbol and quiet zone, resulting in failing grades for modulation and fixed pattern damage on many easy-to-read parts.

AIM DPM-1-2006

The AIM Direct Part Mark Quality Guideline was released in December 2006. The basic differences between ISO/IEC 15415 and AIM DPM-1-2006 are enumerated in Sections 5.1 and 5.2 of the guideline as follows:

5.1 Process Differences from ISO/IEC 15415

All parameters in the symbology and print quality specifications apply except for:

• A different method for setting the image contrast.
• A different method for creating the binary image.
• A new method for choosing the aperture size.
• An image pre-process methodology for joining disconnected modules in a symbol.
• A different process for determining the Modulation parameter renamed Cell Modulation.
• A different process for determining the Symbol Contrast parameter which has been renamed Cell Contrast.
• A different process for computing Fixed Pattern Damage.
• A new parameter called Minimum Reflectance.

This guideline explains how to specify and report quality grades in a manner complementary to, yet distinct from, the method in ISO/IEC 15415.

5.2 Lighting

This guideline recommends three specific lighting environments consisting of two forms of diffuse (non-directional) lighting:

• Diffuse on-axis illumination uses a diffuse light source illuminating the symbol approximately perpendicular to its surface (nominally parallel to the optical axis of the camera).
• Diffuse off-axis illumination uses light from an array of LEDs reflected from the inside of a diffusely reflecting surface of a hemisphere, with the symbol at its center, to provide even incident illumination from all directions.
• Directional illumination is oriented at a low angle (approximately 30 degrees) to the mark surface.

The parameters measured by AIM DPM-1-2006 are:

• Cell Contrast
• Axial Non-Uniformity
• Grid Non-Uniformity
• Unused Error Correction
• Fixed Pattern Damage
• Cell Modulation
• Reference Decode
• Minimum Reflectance

As with other standards, the overall grade is the lowest of any of the sub-grades. Highlights of the physical setup for AIM DPM-1-2006 are:

• The image sensor plane must be parallel to the surface of the part although no tolerance is specified for the parallelism.
• The symbol must be oriented such that one edge is parallel to the side of the image sensor (±5°).
• A specific set of lights must be used for this verification type: 90° (90), dome (D), 30° from four directions (30Q), 30° from two directions (30T) and 30° from one direction (30S).
• The image must be in the best possible focus, but there is no stated focus tolerance.

ISO/IEC 15434 and ISO/IEC 15418

These standards concern the syntax and semantics (formatting) of the string for Data Matrix symbols used in the UID program as specified by the MIL-STD-130. The string must start with the characters "[)>R" with a single byte, thus saving data capacity in the Data Matrix symbol.

This guideline explains how to specify and report quality grades in a manner complementary to, yet distinct from, the method in ISO/IEC 15415.
Application of Verification Standards in MIL-STD-130

During the various releases of the MIL-STD-130, the definition of acceptable Data Matrix marking quality has gone through several stages, and has used parts of each of the standards mentioned earlier in this document. The table below describes the standards referenced in MIL-STD-130 and how they are applied.

<table>
<thead>
<tr>
<th>Date</th>
<th>MIL-STD-130 Version</th>
<th>Verification Standard</th>
<th>Application</th>
</tr>
</thead>
<tbody>
<tr>
<td>Oct. 10, 2003</td>
<td>MIL-STD-130L</td>
<td>ISO/IEC 16022</td>
<td>All marks</td>
</tr>
<tr>
<td>Dec. 2, 2005</td>
<td>MIL-STD-130M</td>
<td>ISO/IEC 15415 then AS9132</td>
<td>Use ICO/IEC 15415 first then AS9132</td>
</tr>
</tbody>
</table>

1. Exceptions to ISO/IEC 15415 in MIL-STD-130:
   - No rotational averaging
   - Contrast and Modulation grades allowed to be as low as “C”
   - 660nm lighting requirement

2. Exceptions to AIM DPM-1-2006 in MIL-STD-130:
   - Dome light not allowed
   - Quad-directional 45° medium-angle light from ISO/IEC 15415 allowed
   - Only applies to direct part marks – not labels

Parameters Used in Verification

Below is a brief description of the parameters used in measuring Data Matrix symbols. Many of these measurements use the concept of the “ideal grid.” This is the equally spaced array of line segments formed by using the four corners and dividing the entire Data Matrix by the number of rows horizontally and columns vertically.

**Angle of Distortion** – The difference from perpendicular of the two solid edges of the Data Matrix, measured in degrees.

**Axial Non-Uniformity** – The difference between the height and the width with respect to the rows and columns.

**Cell Contrast** – In AIM DPM-1-2006, the difference in the population of light pixels to the population of light pixels (see histogram) using the sample principle as “Symbol Contrast” with modified definition.

**Cell Size** – The overall width divided by the number of columns or the overall height divided by the number of rows.

**Cell Modulation** – In AIM DPM-1-2006, a measurement of the uniformity of the color of the dark areas and the light areas of the Data Matrix (see histogram) similar to “Cell Modulation” but differing in implementation.

**Dot Center Offset** – The linear difference of the location of the center of the cell compared to the center of the ideal grid center calculated as a percentage of the nominal cell size.

**Dot Size Offset** – The difference in the apparent size of each individual data element in the Data Matrix.

**Fixed Pattern Damage** – A measurement of the errors in the borders of the Data Matrix as well as any errors in the quiet zone around the symbol necessary for the decoding process.

**Grid Non-Uniformity** – The difference of the measured grid in relation to the ideal grid formed from the four corners of the Data Matrix.

**Matrix Size** – The overall size of the symbol as measured linearly across the width or height.

**Minimum Reflectance** – Lowest reflectance of any sample area in the Data Matrix.

**Modulation** – In ISO/IEC 15415, a measurement of the uniformity of the color of the dark areas and the light areas of the Data Matrix (see histogram) similar to “Cell Modulation” but differing in implementation.

**Module Fill** – The percentage of completeness of the ideal grid.

**Nominal Module Size** – The scalable X-dimension of a typical symbol cell.

**Dot Ovality** – The difference of the widest part of a round cell versus the narrowest part of the cell.
**Print Growth** – The positive or negative size relation of the cells as printed with respect to the ideal grid.


**Symbol Contrast** – The difference in the population of dark pixels to the population of light pixels (see histogram) similar to AIM DPM-1-2006 “Cell Contrast”.

**Unused Error Correction** – The amount of error correction that can be read incorrectly when the symbol is still readable that is currently being read correctly, expressed as a percentage.

*Histogram showing pixel color populations for a bimodal distribution typically found in the Data Matrix symbology.*
## Verification Parameters vs. Standards

### Parameters Measured

<table>
<thead>
<tr>
<th>Parameters Measured</th>
<th>Angle of Distortion</th>
<th>Axial Nonuniformity</th>
<th>Cell Size</th>
<th>Dot Center Offset</th>
<th>Dot Size Offset</th>
<th>Fixed Pattern Damage</th>
<th>Grid Nonuniformity</th>
<th>Minimum Reflectance</th>
<th>Modulation</th>
<th>Module Fill</th>
<th>Nominal Module Size</th>
<th>Ovality</th>
<th>Print Growth</th>
<th>Reference Decode</th>
<th>Symbol Contrast</th>
<th>Unused Error Correction</th>
</tr>
</thead>
</table>

### Standards and Dates

<table>
<thead>
<tr>
<th>Standard</th>
<th>Date</th>
</tr>
</thead>
<tbody>
<tr>
<td>ISO/IEC 16022</td>
<td>May 2000</td>
</tr>
<tr>
<td>ISO/IEC 15415</td>
<td>June 2004</td>
</tr>
<tr>
<td>AS9132 Laser Etch</td>
<td>Feb. 2002</td>
</tr>
<tr>
<td>AS9132 Dot Peen</td>
<td>Feb. 2002</td>
</tr>
<tr>
<td>AS9132 Electrochem Etch</td>
<td>Feb. 2002</td>
</tr>
<tr>
<td>AIM DPM-1-2006</td>
<td>Dec. 2006</td>
</tr>
</tbody>
</table>

### Applicability - MIL-STD-130

<table>
<thead>
<tr>
<th>Applicability</th>
<th>MIL-STD-130</th>
</tr>
</thead>
<tbody>
<tr>
<td>Labels</td>
<td>130L</td>
</tr>
<tr>
<td>All</td>
<td>130L Chg.1/130M</td>
</tr>
<tr>
<td>Laser DPM</td>
<td>130L Chg.1/130M</td>
</tr>
<tr>
<td>Dot DPM</td>
<td>130L Chg.1/130M</td>
</tr>
<tr>
<td>EC Etch DPM</td>
<td>130L Chg.1/130M</td>
</tr>
<tr>
<td>DPM</td>
<td>130M Chg.1/130N</td>
</tr>
</tbody>
</table>

---

**MICROSCAN.**

[www.microscan.com](http://www.microscan.com)

**North America (Corporate Headquarters)**

Email: info@microscan.com

**Europe**

Email: info@microscan.nl

**Asia Pacific**

Email: asia@microscan.com